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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

APPLICANT: Won-Sung Choi)
SERIAL NO.: 09/726,977)
FILED: November 30, 2000)
FOR: THIN FILM DEPOSITION APPARATUS)
FOR SEMICONDUCTOR)

) Group Art No.: 1763
)
) Examiner:
) Kackar, Ram N.

#10B
1/1

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Assistant Commissioner for Patents
Washington, D.C. 20231

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SUBMISSION UNDER 37 C.F.R. §1.114

This submission, in the form of an amendment with remarks, is filed under 37 C.F.R. §1.114 along with a Request for Continued Examination (RCE) and requisite fee. Grant of the Request, entry of the amendment, reconsideration of the claims, and allowance of the application are respectfully requested.

AMENDMENT

IN THE CLAIMS:

Please cancel claim 5, without prejudice.

Please replace claims 1-3, 6-13, 15 and 16 with the following claims rewritten in clean form:

- B1
1. (Twice Amended) A semiconductor thin film deposition apparatus comprising:
a reactor in which a wafer is received;
a reaction gas supply unit for providing reaction gas to the reactor;